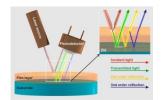
Film Metrology & More...

ThetaMetrisis APPLICATION NOTE #036

Suspended Active-Silicon membrane thickness measurements for MEMS applications, at a 25um spot size.



Introduction: Silicon-based sensors have been broadly implemented in different MEMS applications for their high-performance, low cost and small size. Thickness determination of the active-Si layer either suspended on patterned Si membranes or on SOI based sensors is crucial for the control of the performance of the final platform [1]. Here we have measured such film thicknesses on a MEMS pressure sensor, using the **FR-μProbe** tool with a 250μm aperture size, attached on a Leica DM LM optical microscope. Measurements performed using the 10X objective lens, which along with the selected aperture size, corresponds to a **25μm spot size (area of measurement)**.

Means and Methods: Typical experimental reflectance spectra (black line) obtained, and fitted reflectance spectra (red line) as recorded by the FR-Monitor software, are illustrated in the figures below. Figure 1, shows measurement on the SOI area of the sensor, where simultaneous thickness measurement of Active-Silicon and the Buried Oxide was performed. The thickness value of the SiO₂ thin film measured at 759.2nm, while the Si film on top at 5320.1 nm.

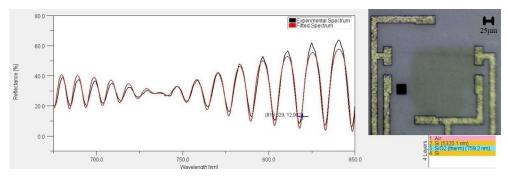


Figure 1. Experimental and fitted reflectance spectra of the SOI area on a MEMS pressure sensor and the thickness values measured.

Figure 2, shows measurement on the patterned suspended Silicon area of the sensor, where again the simultaneous thickness measurement of Active-Si and Buried Oxide was performed. The thickness value of the SiO₂ thin film measured to be the same at **759.2nm**, while the Si film on top at **5329.1 μm**, **9nm higher** than in the SOI area.

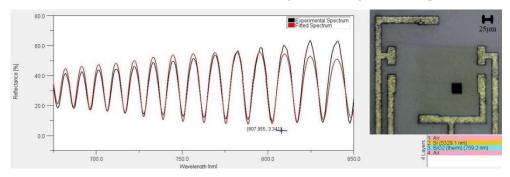


Figure 2. Experimental and fitted reflectance spectra of the suspended Silicon area on a MEMS pressure sensor and the thickness values measured.

Concussions: ThetaMetrisis' **FR-uProbe** tool is a unique powerful tool for the local measurement of thickness(es) of layers with spot size down to $2\mu m$. Thanks to its modular design can be attached on any trinocular optical microscope enhancing this way the microscope capabilities without any effect on its performance.

References:

[1] J. Su, X. Zhang, G. Zhou, C. Xia, W. Zhou, and Q. Huang, "A review: crystalline silicon membranes over sealed cavities for pressure sensors by using silicon migration technology," J. Semicond., vol. 39, no. 7, pp. 1–7, 2018.